OK TO ENTER: /CH/

12/17/2008

SHIGA7.029APC

PATENT

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant

: Hojo et al.

Appl. No.

: 10/553,083

Filed

: October 11, 2005

For

: POSITIVE RESIST

COMPOSITION AND METHOD OF FORMATION OF RESIST

PATTERN

Examiner Group Art Unit

: C. Hamilton : 1752

AMENDMENT AND RESPONSE TO FINAL OFFICE ACTION

Commissioner for Patents - Box AF P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed October 15, 2008, please consider the following amendments and remarks.

Amendments to the claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 5 of this paper.